

INFORMATION DISCLOSURE STATEMENT BY APPLICANT	ATTY. DOCKET NO. 2345/108	SERIAL NO. 09/462,283
	APPLICANT Hans Wilfried Peter KOOPS	
	FILING DATE Jan. 5, 2000	GROUP 1746 To be assigned

U. S. PATENT DOCUMENTS

EXAMINER INITIAL	PATENT NUMBER	PATENT DATE	NAME	CLASS	SUBCLASS	FILING DATE
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FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
	196 16 324*	October 30, 1997	Germany				
	0 614 126*	September 7, 1994	Europe				
	63 249837*	October 17, 1988	Japan				
SA	24 46 789**	September 2, 1976	Germany				
↓	24 60 716**	May 6, 1976	Germany				
	24 60 715**	June 24, 1976	Germany				
↓	25 15 550**	October 7, 1976	Germany				

* Copy of Reference is not enclosed because reference is cited in Search Report (copy of reference provided by International Searching Authority).
 ** Mentioned in the Specification.

OTHER DOCUMENTS

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EXAMINER	Shamim Ahmed	DATE CONSIDERED	7/24/01
EXAMINER: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.			